PREPARATION METHOD



Pressure parameters and specimen size

Magnesium based alloys

Recommended machines and additional consumables (not included)

Equipment ATM Brillant	Consumables Cut-off wheel: diamond, resin bond Anti-corrosion coolant	Specimen diameter [mm]	25	30	40	50	60
Equipment ATM Opal	Consumables Hot mounting: Bakelite red/black/green Cold mounting: KEM 20 Hot or cold mounting	Divergence in pressure used in the preparation methods	-(5 N10 N)	-5 N	0	+5 N	+(5 N10 N)
Sample size Ø 40 mm							

Notes:

STEP		MEDIUM	2×.	T rpm	*	Single Pressure		
୭	Planar grinding	SiC-paper/foil P320 (280)*	H ₂ O	250-300	Synchronous Rotation	15	Until plane	
୭	Planar grinding	SiC-paper/foil P800 (280)*	H ₂ O	250-300	Synchronous Rotation	15	1:00	
ଚ	Planar grinding	SiC-paper/foil P1200 (280)*	H ₂ O	250-300	Synchronous Rotation	15	1:00	
\Leftrightarrow	Polishing	ВЕТА	Diamond suspension (alcohol or oil based Poly, 9 µm	120-150	Synchronous Rotation	15	5:00	
\Leftrightarrow	Polishing	SIGMA	Diamond suspension (alcohol or oil based Poly, 3 µm	120-150	Synchronous Rotation	15	5:00	
\Leftrightarrow	Polishing	ZETA	Diamond suspension (alcohol or oil based Poly, 1 μm	120-150	Synchronous Rotation	15	5:00	
\oslash	Final polishing	OMEGA**	Etosil E, 0.06 μm**	120-150	◄► Counter Rotation	25	4:00 (ethanol during final 0:30)	
\oslash	Optional: Final polishing	OMEGA Saphir Vibro	Etosil E, 0.06 μm**				20:00	
	Optional: Etching (chem.)	Nital 3%***					Approx. 0:03-0:10 (ethanol for 0:30)	

Coat grinding paper/foil with paraffin wax before grinding to reduce the contamination of the sample by SiC particles
 Wet the OMEGA polishing cloth with ethanol before polishing
 *** ATM Item No. 95005033

BEGINNERS GUIDE		Notes:
	Use suitable cut-off wheels for magnesium material (e.g. ATM FS-A wheels) Constant cutting speed max. 0.25 mm/s	
	Use mounting material with high edge retention Hot or cold mounting both possible	
GRINDING GRINDING S G G G G G G G G G G G G G	Coat grinding paper/foil with paraffin wax before grinding to reduce the contamination by SiC particles Start grinding with SiC-paper/foil P320 (280) Continue with P800 and P1200 Thoroughly wash samples and holder under running water after each grinding step	
POLISHING • E • C • C • C • C • C • C • C • C • C • C	Rinse the polishing discs with water and spin dry after use Do not stack discs with different diamond sizes Clean samples, holders and hands under running water before each polishing step Use ethanol and blow dryer to avoid water stains Check after each step under the microscope if polishing marks are of equal size and randomly oriented Wet the OMEGA polishing cloth with ethanol before polishing Use the consumables only for magnesium based alloys and not for other materials Rinse the spray nozzle of the Etosil E bottle after use, put cap on nozzle	

SAMPLE MICROGRAPHS

OK Sample polished	NOK Sample polished				
20x micrograph of magnesium after OMEGA polishing	20x micrograph of magnesium after Etosil polishing	20x micrograph of magnesium etched with Nital			
 No traces of scratches Clean homogeneous surface 	 Sparse scratches from 0.06 µm Eposal after OMEGA 	 No traces of scratches Clear structure 			

- Pores and inclusions with perfect edges



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